

Polymer Conductivities

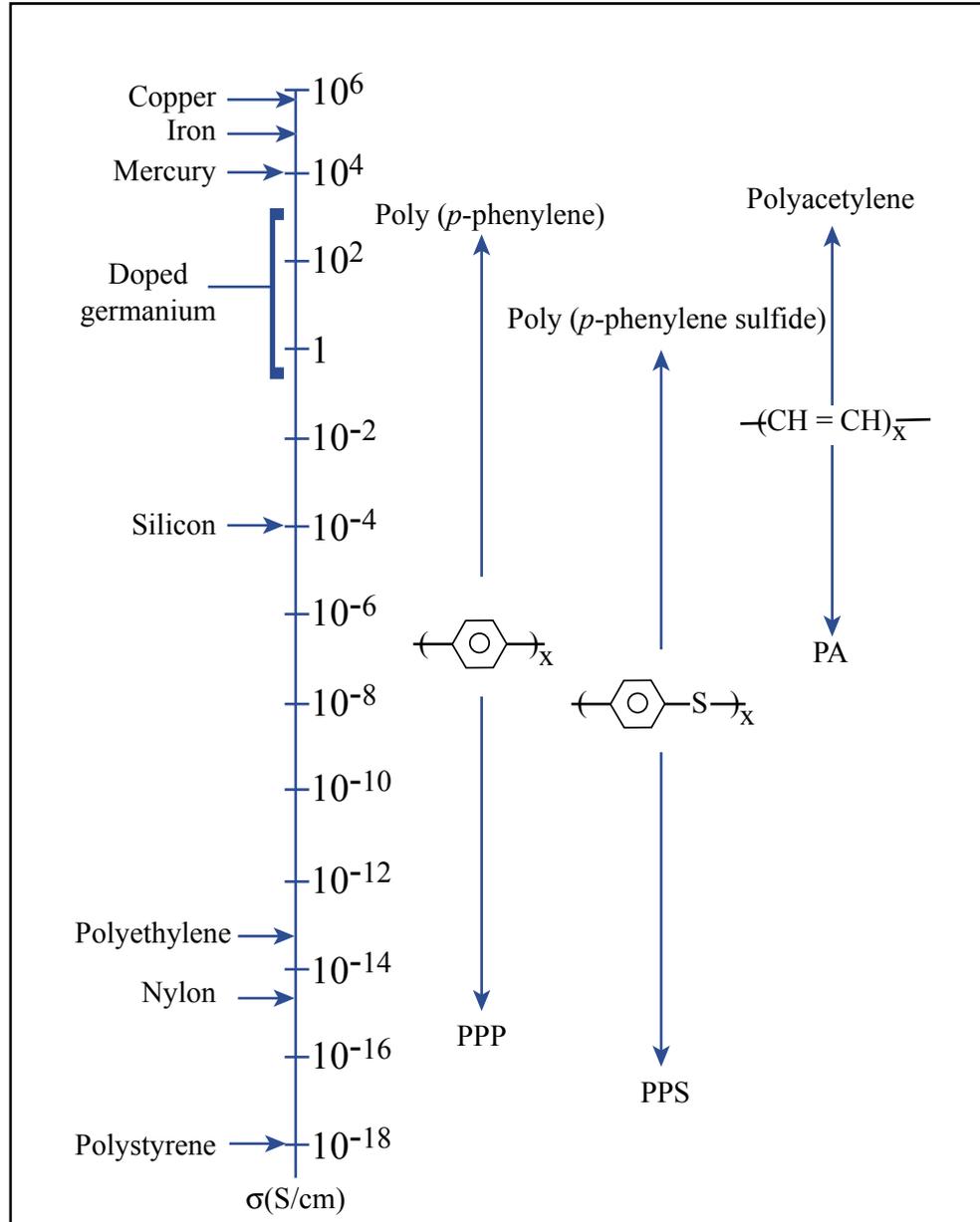
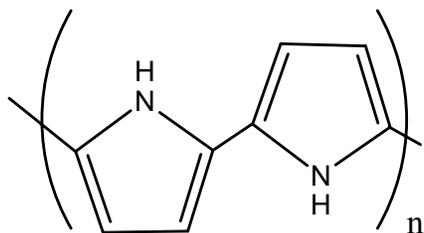


Figure by MIT OCW.

Polypyrrole Actuator

- Low voltage required to operate (< 2 V)
- High power density (150 W/kg)
- High active stress (10 - 40 MPa)
- Moderate active strain (2 - 10%)
- Light and Flexible

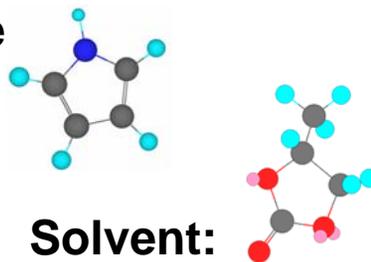
Polypyrrole
Chemical Structure



Deposition Solution Components:

Monomer:

Pyrrole

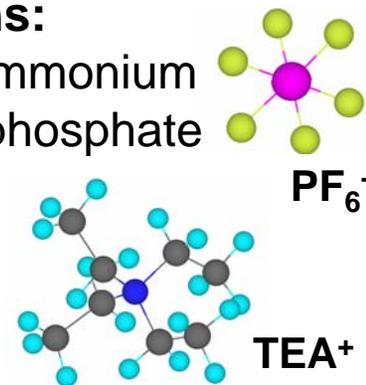


Solvent:

Propylene Carbonate

Counterions:

Tetraethylammonium
Hexafluorophosphate
(TEA-PF6)

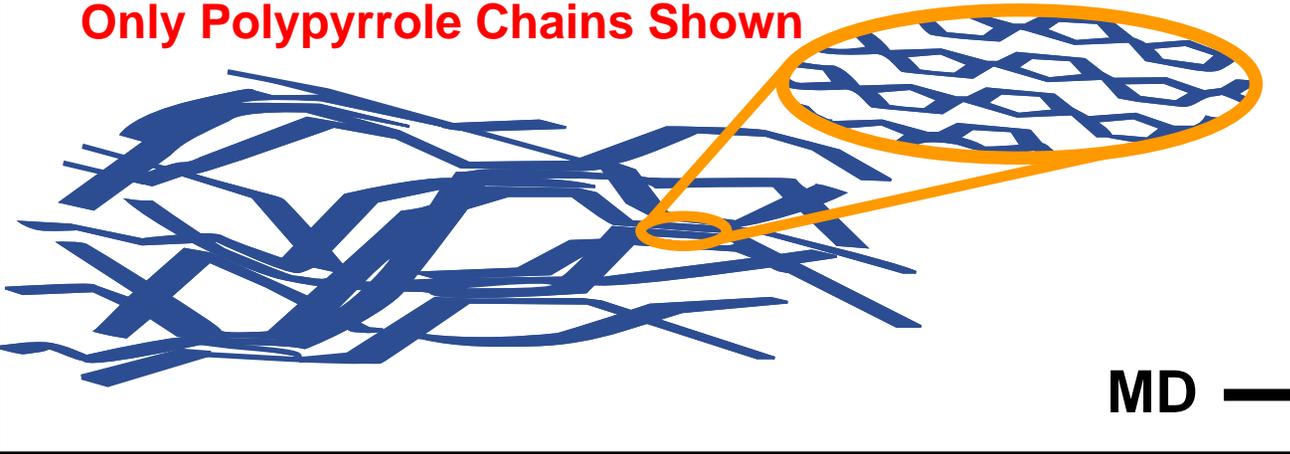


PF₆⁻

TEA⁺

Polypyrrole Microstructure

Only Polypyrrole Chains Shown



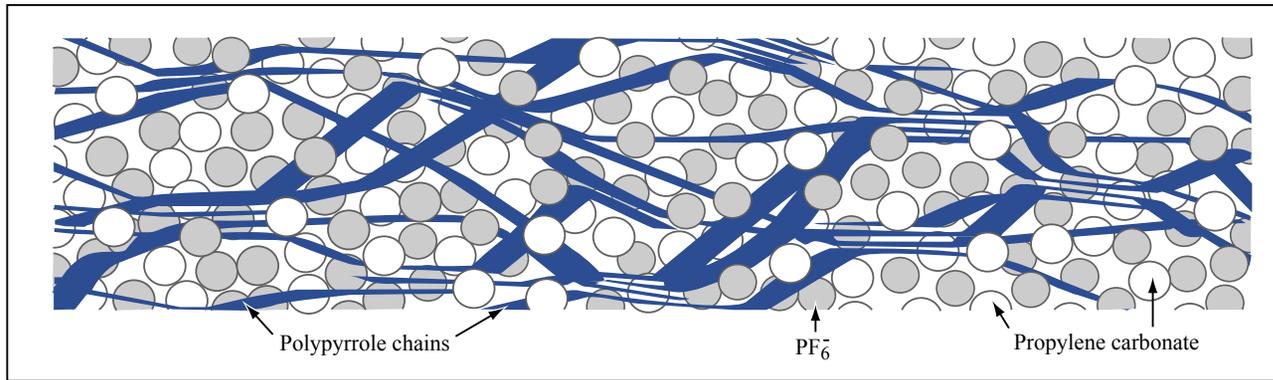
Polypyrrole has disordered rigid chains held together by small, π -stacked bundles.

Figure by MIT OCW.

- Bundles do not give rise to crystalline peaks in x-ray, but do cause certain characteristic reflections
- Bundles consist of π -stacked segments and serve as pseudo-crosslinks, keeping the material insoluble and unmeltable
- Bundles allow percolative path of rigid, electronically conductive chains through bulk sample
- Solvent and counterions are randomly distributed outside of bundles. They act as plasticizers for the film.
- Actuation occurs when polymer conducts charges/discharges and counterions enter and leave the disordered regions between bundles.

Polypyrrole Microstructure

Stretched Film Components

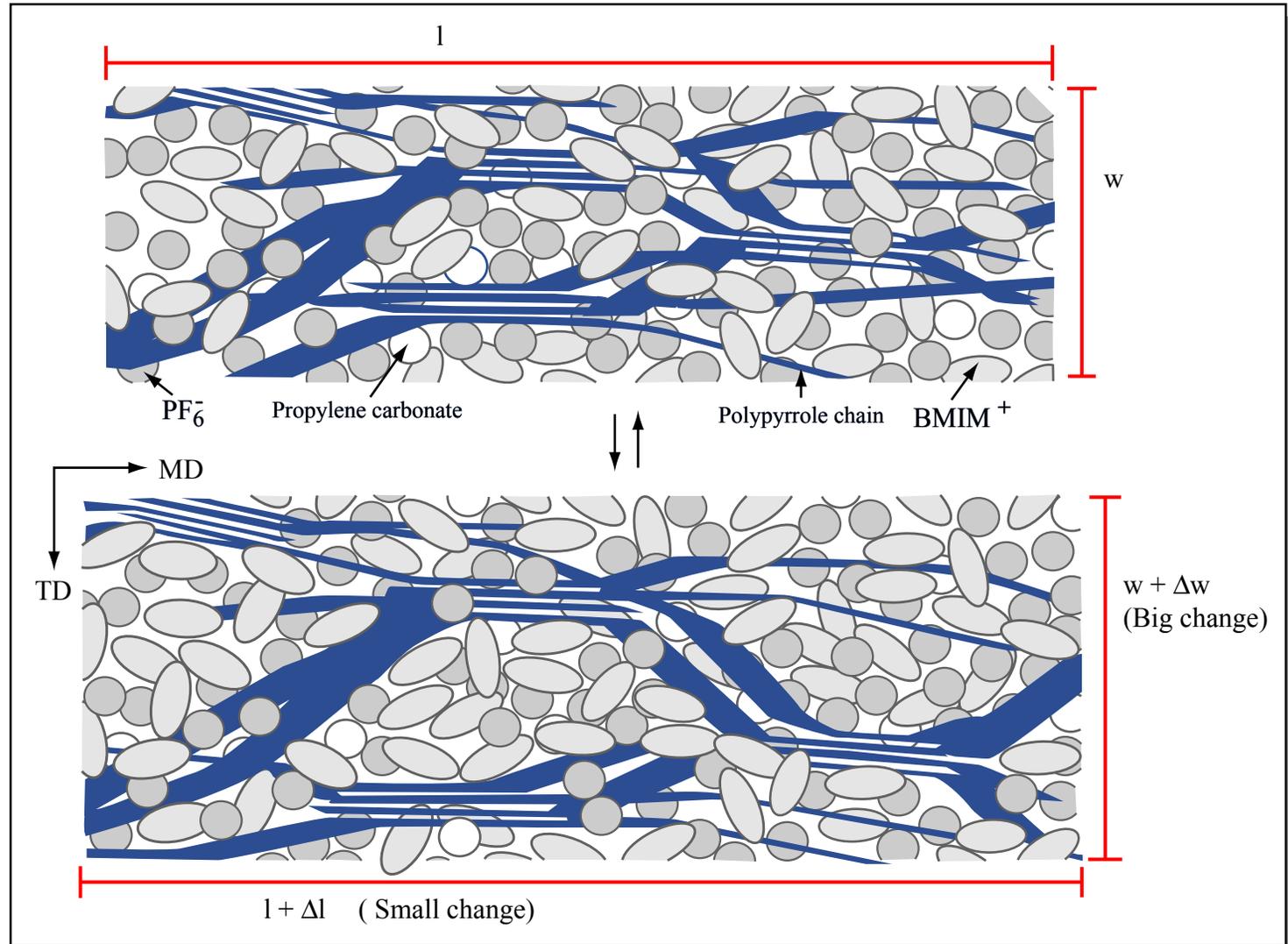


As-deposited film is
~40% polypyrrole,
30% propylene
carbonate and 30%
PF₆⁻

Figure by MIT OCW.

- As polymerized film has polypyrrole chains positively charged, **PF₆⁻** anions are present at a ratio of about 1 anion per 3 monomeric repeats of the pyrrole chain.
- Solvent and counter anions are homogeneously distributed outside of pyrrole bundles.
- Actuation (expansion) occurs when more electrons are removed (oxidation) from pyrrole backbone and more anions enter to maintain charge neutrality.
- Actuation (contraction) occurs when more electrons are added (reduction) to the pyrrole backbone and some anions leave to maintain charge neutrality.

Mechanism of Actuation in Oriented Pyrrole Films

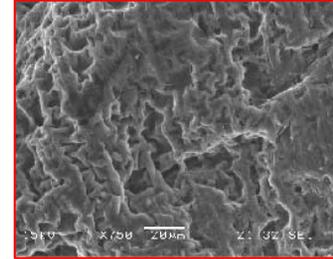


Actuation of Different Recipes

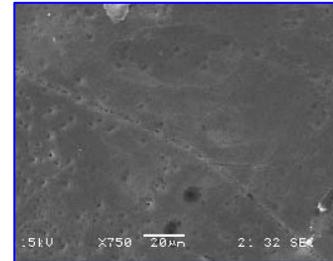
Potential (V) or Strain (%)

Images of polypyrrole morphology and voltage-strain curves removed due to copyright restrictions.

**TBA-TFSI/MB
on Ni**
 $\sigma = 3.6 \times 10^3 \text{ S/m}$
 $E = 40 \text{ MPa}$



**TBA-TFSI/MB
on GC**
 $\sigma = 2.5 \times 10^4 \text{ S/m}$
 $E = 240 \text{ MPa}$



Surface morphology

Recipe	Contraction (%) at $\pm 0.8\text{V}$ in:	
	10 sec	60 sec
TBA-TFSI/MB on GC	2.05	5.22
TBA-TFSI/MB on Ni	2.75	4.27

One has to find a balance between fast and large active strains

Potential

Polypyrrole Actuation

Isometric Testing

- Apply constant strain to polymer strip, measure active stress

Isometric: $\varepsilon_0 = 1\%$

Applied
Potential (V)

Measured
Current (mA)

Calculated
Charge (mC)

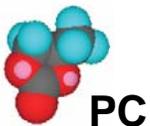
$q(t)$

Measured
Stress (MPa)

$\sigma(t)$

Images of polypyrrole actuation and various data removed due to copyright restrictions.

Actuation Solution: 0.1M LiTFSI in PC



Optical Properties of Materials

1. Linear, homogeneous, isotropic, nondispersive media

P = polarization density

E = electric field

ϵ_0 = dielectric permittivity

χ = scalar constant \equiv electric susceptibility

n = index of refraction = c/v

$$\vec{P}(\vec{r}, t) = \epsilon_0 \chi \vec{E}(\vec{r}, t)$$

c = speed of light in vacuum,

v = speed of light in material

$$n = \left(\frac{\epsilon}{\epsilon_0} \right)^{1/2} = (1 + \chi)^{1/2}$$

2. Inhomogeneous medium

$$n = n(\vec{r}) \quad \chi = \chi(\vec{r}) \quad \epsilon = \epsilon(\vec{r})$$

position dependent, due to variation of material properties

(e.g. oriented glassy polymer via injection molding, photonic crystal, etc.)

3. Anisotropic medium: the electric susceptibility is a 2nd rank tensor

$$P_i = \sum_j \epsilon_0 \chi_{ij} E_j$$

By a suitable choice of coordinate system, χ_{ij} can be made so that off-diagonal elements are zero. χ_{11} , χ_{22} , χ_{33} define the principal susceptibilities along the principal axes.

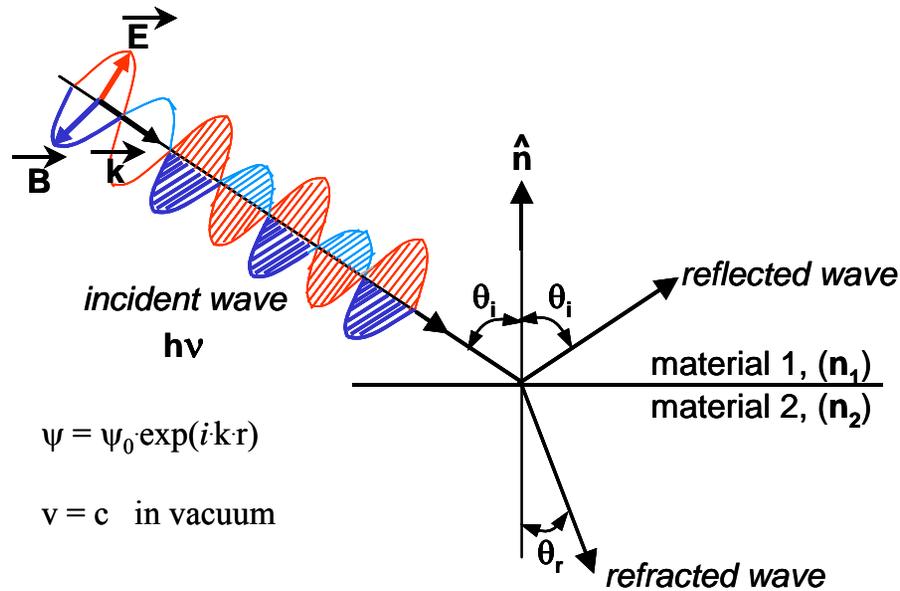
4. Absorption

$$\chi = \chi' + i\chi''$$

complex susceptibility

Optical Properties

Interaction of E-M Radiation with Polymers



Possible Interactions:

1. reflection
2. refraction
3. absorption
4. polarization change

$$n = n_R - in_i$$

$$\text{Re}(n) = n_R$$

$$\text{Im}(n) = n_i \equiv \text{absorption}$$

Materials Interaction with E-M Radiation

1. Reflection

- **Law of Reflection:** the incident and reflected wave are in the same plane (of incidence) and they make an angle θ_i with the normal on the interface between the 2 materials.

2. Refraction

- **Snell's Law of Refraction:** $n_1 \sin(\theta_i) = n_2 \sin(\theta_r)$
- it is possible to determine n_2 if n_1 known (for air $n = 1$), by measuring θ_i, θ_r .
- **Origin of Refractive Index:** given by the polarizability of the material, interaction of incident light with rapid oscillating electrons in the material (especially valence electrons).

For neutral molecules:
$$\frac{n^2 - 1}{n^2 + 2} = \frac{1}{3\epsilon_0} \sum_i N_i \alpha_i \quad (\text{Lorenz - Lorentz equation})$$

n = refractive index,

α_i = polarizability of the i^{th} chemical bond

N_i = number of i^{th} type chemical bond

3. Absorption

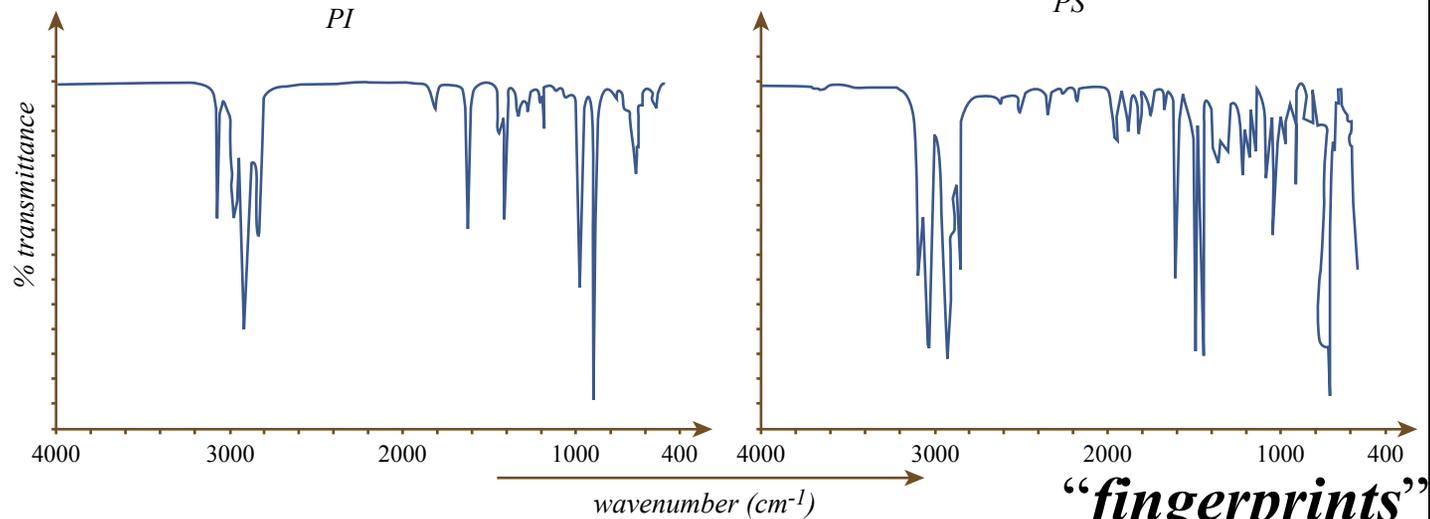
- when the frequency of the incident wave is close to the frequency of a certain oscillations in the material:

- e.g. IR - vibrations of atoms / chemical bonds (basis for IR spectroscopy which identifies atomic groups based on characteristic vibrations)
- UV - electronic transitions between different energy levels (in quantum mechanics see electrons as waves, different energies, different frequencies)

Absorption is maximum at resonance (when the frequency of the incident wave equals the frequency of a particular oscillation in the material) and when the direction of polarization is along the direction of vibration

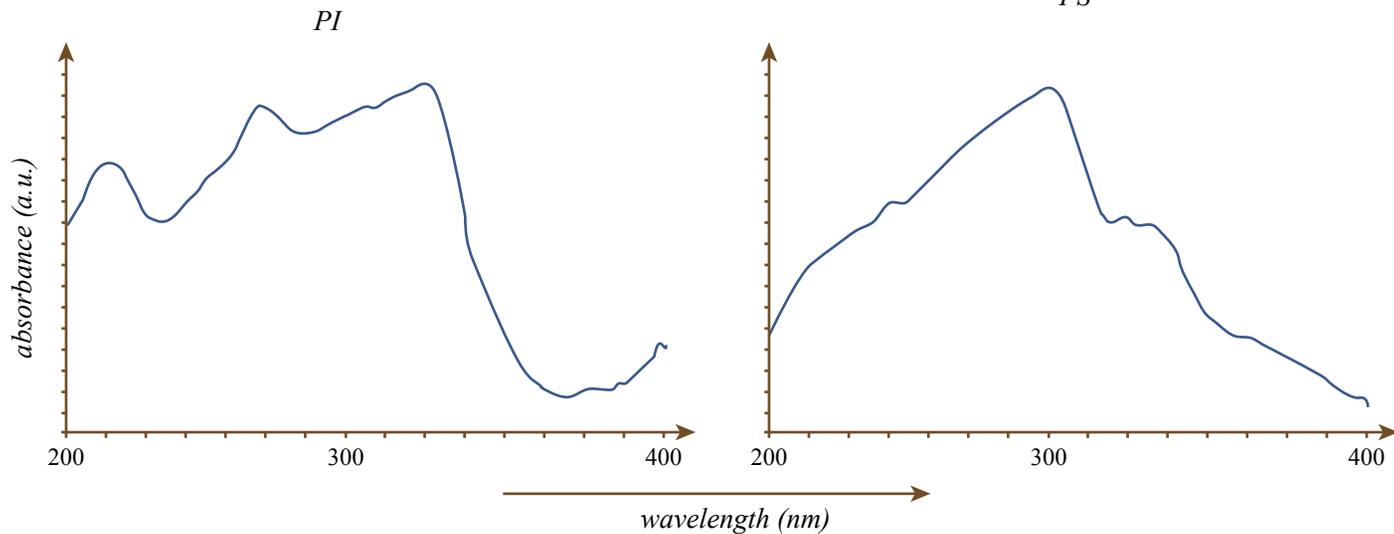
Absorption of Polymers in IR and UV

IR:



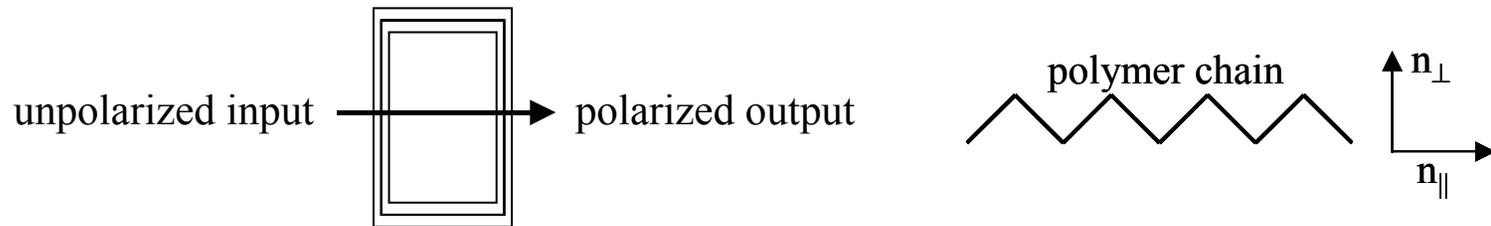
“fingerprints”

UV:



4. Polarization Change

Methods of Producing Polarized Light



1. Selective Dichroism—oriented polymer matrix with aligned guest dye molecules (Edwin Land)
2. Birefringence

Q: how does a LCD pixel work?

- orientational birefringence: alignment of optically anisotropic molecules

$$\Delta = n_{\parallel} - n_{\perp}$$

- strain birefringence: applied stress alters bond distances which alters polarizability along stress direction. Can occur in an isotropic medium subject to stress.
- form birefringence: material comprised of two or more components with different indices of refraction with shape anisotropy of at least one of the components (e.g. cylindrical microdomains in roll cast BCP). Domains must be on the scale of the wavelength or larger

Nonlinear Optical Materials

$$\vec{P}_i = \chi_{ij}^{(1)} \vec{E}_j + \chi_{ijk}^{(2)} \vec{E}_j \vec{E}_k + \chi_{ijkl}^{(3)} \vec{E}_j \vec{E}_k \vec{E}_l$$

alternatively can write in terms of molecular susceptibility per unit volume

$$\mu_i = \alpha_{ij} E_j + \beta_{ijk} E_j E_k + \gamma_{ijkl} E_j E_k E_l$$

α_{ij} = molecular susceptibility

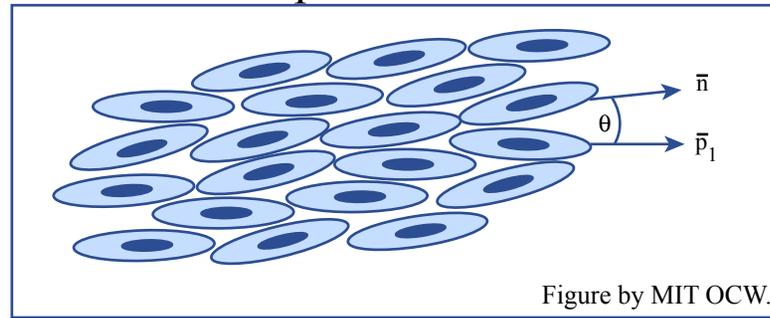
β_{ijk} = nonlinear molecular susceptibility of order 2 (3rd rank tensor)

γ_{ijkl} = nonlinear molecular susceptibility of order 3 (4th rank tensor)

the β and γ terms depend on the number of molecules per unit volume and their orientation.

$$\chi^{(2)} \sim \beta \langle \cos^3 \theta \rangle$$

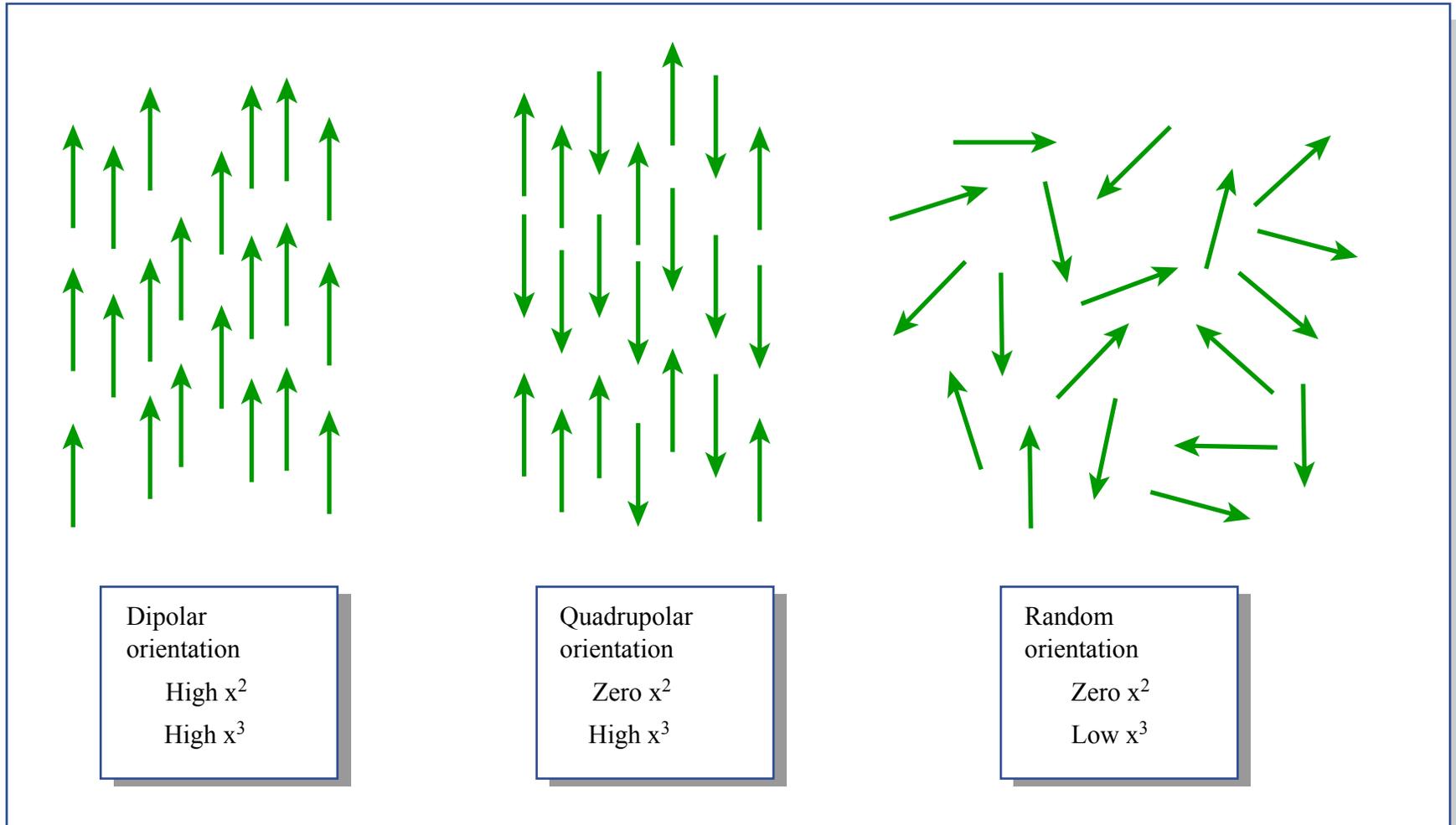
$$\chi^{(3)} \sim \gamma \langle \cos^4 \theta \rangle$$



$\chi^{(2)}$ is zero for centrosymmetric orientation of an array of dipoles since $\cos^3 0^\circ = 1$
but $\cos^3 180^\circ = -1$ so averages to zero

$\chi^{(3)}$ can be nonzero for centrosymmetric systems

Influence of Different Orientational States on NLO Parameters



Frequency Doubling

$$\vec{P}_i = \chi_{ij}^{(1)} \vec{E}_j + \chi_{ijk}^{(2)} \vec{E}_j \vec{E}_k + \chi_{ijkl}^{(3)} \vec{E}_j \vec{E}_k \vec{E}_l$$

Second-Order NLO Materials

$$|\vec{P}_{NL}| = \epsilon_o \chi^{(2)} |E|^2 \quad \text{where } |\vec{P}_{NL}| \text{ is the magnitude of the 2}^{\text{nd}} \text{ order nonlinearity}$$

assume $E(z,t) = E_o \cos(2\pi\nu t - kz)$

then $|\vec{P}_{NL}| = \frac{\epsilon_o}{2} \chi^{(2)} E_o^2 (1 + \cos(4\pi\nu t - 2kz)) = P_{NL}(0) + P_{NL}(2\nu)$

DC \downarrow frequency doubled \swarrow

The term $\vec{P}_{NL}(2\nu)$ is the source for radiation @ twice the input frequency. This is called second harmonic generation (SHG).

Note that $\chi^{(2)}$ is zero for all centrosymmetric structures. This means SHG samples need to be strongly poled to align the dipoles.

Frequency Tripling

Third-Order NLO Materials

Centrosymmetric materials at very high applied fields, $\chi^{(2)} = 0$, but $\chi^{(3)} \neq 0$

$$\begin{array}{l} \left| \vec{P}_{NL} \right| = \varepsilon_0 \chi^{(3)} |E|^3 \\ \left| \vec{P}_{NL} \right| = \frac{\varepsilon_0}{4} \chi^{(3)} E_0^3 \left(3 \cos(2\pi\nu t - 2kz) + \cos(6\pi\nu t - 3kz) \right) \end{array}$$

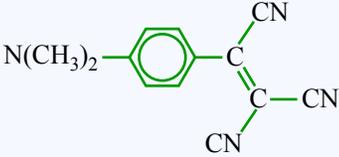
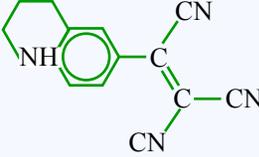
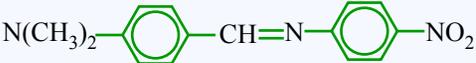
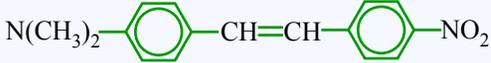
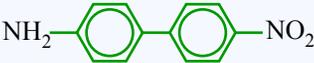
intensity modulation of incident ν frequency tripled (THG)

The polarization component at incident frequency ν , $\vec{P}_{NL}(2\nu)$ has changed due to interaction of the light with the NLO material.

This corresponds to an incremental change in susceptibility: $\Delta\chi$

$$\begin{aligned} \Delta\chi &= \frac{P_{NL}(\nu)}{E(\nu)} = \frac{\frac{3}{4}\varepsilon_0 \chi^{(3)} E_0^3 \cos(2\pi\nu t - kz)}{E_0 \cos(2\pi\nu t - kz)} \\ &= \frac{3}{4}\varepsilon_0 \chi^{(3)} E_0^2 \end{aligned}$$

NLO Chromophores Values, β

STRUCTURE	β at 1.9 μm $\times 10^{-30}$ esu
	5.7
	21.4
	41.8
	23.4
	60.0
	20.1
	50.7
	111.2

Pendant Chromophores

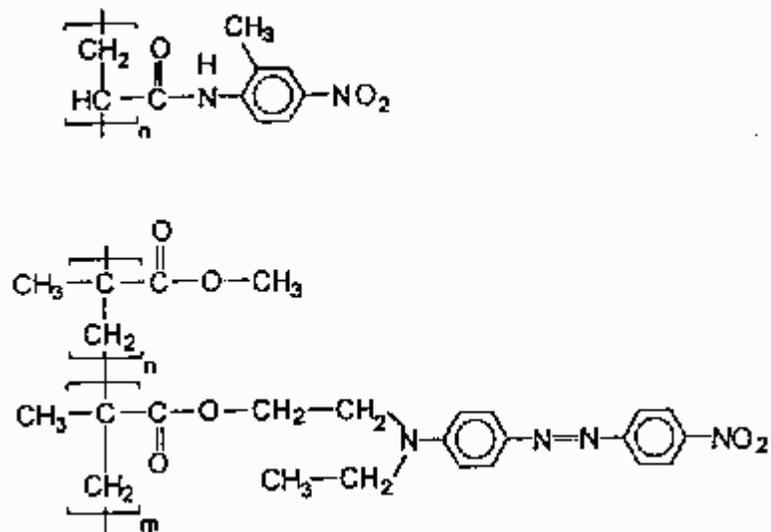


Figure by MIT OCW.

“All-Optical Switching”

“Use light to switch light”

- Employ optical materials with intensity dependent properties:

$$n(I) = n_0 + n_2 I$$

Q: sensor protection?

- Nonlinear phase shift:

$$\phi_{NL} = (2\pi/\lambda)(n_2 I)L$$

- Fast: light switching light

illuminate

